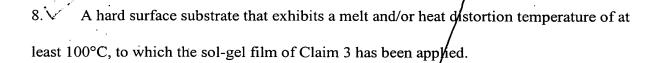


## **CLAIMS**

What we claim is:

- 1. An antimicrobial sol-gel film comprising at least one inorganic antimicrobial agent, wherein said film exhibits a log kill rate for *Klebsiella pneumoniae* of at least 0.5 as measured under a modified plate contact method.
- 2. The antimicrobial sol-gel film of Claim 1 wherein said film exhibits a log kill rate for Klebsiella pneumoniae of at least 1.0.
- 3. The antimicrobial sol-gel film of Claim 2 wherein said film exhibits a log kill rate for *Klebsiella pneumoniae* of at least 2.0.
- 4. The antimicrobial sol-gel film of Claim 3 wherein said film exhibits a log kill rate for *Klebsiella pneumoniae* of at least 3.0.
- 5. The antimicrobial sol-gel film of Claim 4 wherein said film exhibits a log kill rate for Klebsiella pneumoniae of at least 3.5.
- 6. A hard surface substrate that exhibits a melt and/or heat distortion temperature of at least 100°C, to which the sol-gel film of Claim 1 has been applied.
- 7. A hard surface substrate that exhibits a melt and/or heat distortion temperature of at least 100°C, to which the sol-gel film of Claim 2 has been applied.

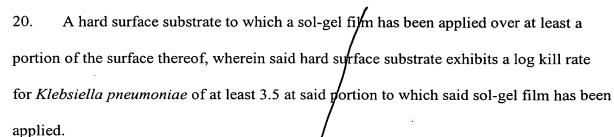


- 9. A hard surface substrate that exhibits a melt and/or/heat distortion temperature of at least 100°C, to which the sol-gel film of Claim 4 has been applied.
- 10. A hard surface substrate that exhibits a melt and/or heat distortion temperature of at least 100°C, to which the sol-gel film of Claim 5 has been applied.
- 11. A hard surface substrate that exhibits a melt and/or heat distortion temperature of at least 300°C, to which the sol-gel film of Claim 1 has been applied.
- 12. A hard surface substrate that exhibits a melt and/or heat distortion temperature of at least 300°C, to which the sol-gel film of ¢laim 2 has been applied.
- 13. A hard surface substrate that exhibits a melt and/or heat distortion temperature of at least 300°C, to which the sol-gel film of Claim 3 has been applied.
- 14. A hard surface substrate that exhibits a melt and/or heat distortion temperature of at least 300°C, to which the sol-get film of Claim 4 has been applied.





- 15. A hard surface substrate that exhibits a melt and/or heat distortion temperature of at least 300°C, to which the sol-gel film of Claim 5 has been applied.
- 16. A hard surface substrate to which a sol-gel film has been applied over at least a portion of the surface thereof, wherein said hard surface substrate exhibits a log kill rate for *Klebsiella pneumoniae* of at least 0.5, as measured under a modified plate contact method, at said portion to which said sol-gel film has been applied.
- 17. A hard surface substrate to which a sol-gel film has been applied over at least a portion of the surface thereof, wherein said hard surface substrate exhibits a log kill rate for *Klebsiella pneumoniae* of at least 1.0 at said portion to which said sol-gel film has been applied.
- 18. A hard surface substrate to which a sol-gel film has been applied over at least a portion of the surface thereof, wherein said hard surface substrate exhibits a log kill rate for *Klebsiella pneumoniae* of at least 2.0 at said portion to which said sol-gel film has been applied.
- 19. A hard surface substrate to which a sol-gel film has been applied over at least a portion of the surface thereof, wherein said hard surface substrate exhibits a log kill rate for *Klebsiella pneumoniae* of at least 3.0 at said portion to which said sol-gel film has been applied.



- Sulpi /
- 21. The hard surface substrate of Claim 18 exhibiting the same log kill rate after said substrate has been immersed in a heated caustic bath, having a pH level of at least 12, for 48 hours.
- 22. The hard surface substrate of Claim 19 exhibiting the same log kill rate after said substrate has been immersed in a heated caustic bath, having a pH level of at least 12, for 48 hours.
- 23. The hard surface substrate of Claim 20 exhibiting the same log kill rate after said substrate has been immersed in a heated caustic bath, having a pH level of at least 12, for 48 hours.